

(Rev. 2-32) PATENT AND TRADEMARK OFFICE
CHEMICAL-ORGANIC PLANARIZATION PROCESS FOR
ATOMICALLY SMOOTH INTERFACES

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APPLICANT

Gerald T. Mearini and Laszlo Takacs

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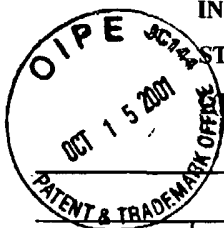
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U.S. PATENT DOCUMENTS

EXAMINER INITIAL	DOCUMENT NUMBER	DATE	NAME	CLASS	SUB- CLASS	FILING DATE IF APPROPRIATE
RRB	5 7 4 8 3 5 0	5/5/98	Pan et al	359	130	6/19/96
↑	6 2 0 5 2 7 0	3/20/01	Cao	385	24	9/23/99
	6 2 3 3 2 6 1	5/15/01	Mesh et al	372	32	6/9/99
	5 5 2 9 6 7 1	6/25/96	Debley et al.	204	192.34	7/27/94
	5 7 2 5 4 1 3	3/10/98	Malshe et al	451	41	5/6/94
	4 7 4 7 9 2 2	5/31/88	Sharp	204	192.11	3/25/86

FOREIGN PATENT DOCUMENTS

DOCUMENT NUMBER	DATE	COUNTRY	CLAS S	SUB- CLAS S	TRANSLATIO N YES NO

OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)

	Kumar, et al.; <i>Near-Infrared Bandpass Filter from Si/SiO₂</i> ; Multilayer Coatings; February 1999
	Suntola, T.; <i>Cost-Effective Processing by Atomic Layer Epitaxy</i> ; 1993
	Bachman, et al.; <i>Molecular Layer Epitaxy by Real-Time Optical Process Monitoring</i> ; Department of Materials Science and Engineering, North Carolina State University, 1997.
	H., Kawai, T. Tabata; <i>Atomic Layer Control of the Growth of Oxide Superconductors Using Laser Molecular Beam Epitaxy</i> ; 1997.
	Spiller, E.; <i>Smoothing of Multilayer X-Ray Mirrors by Ion Polishing</i> ; IBM Research Division, Thomas J. Watson; 1993.
	Puik, E.J., van der Wiel and Zeijlemaker, H. and Verhoeven, J.; <i>Ion Etching of Thin W Layers: Enhancing Reflectivity of W-C Multilayer Coatings</i> ; March 30, 1989.
	Nishizawa, J., Abe, H., and Kurabayshi, T.J. 132(5) (1985).
	Puik, E.J., et al.; <i>Appln. Surf. Sci.</i> 47 (1991) 251.
RRB	Kloidt, A, et al.; <i>Thin Sol Films</i> , 228 (1993) 154.

EXAMINER

R Burch

DATE CONSIDERED

6-24-04

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OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)

RRB	Imai, F., Kunimori, K., and Nozoye, H; <i>Novel Epitaxial Growth Mechanism of Magnesium Oxide/Titanium Oxide Ceramics Superlattice Thin Films Observed by Reflection High-Energy Electron Diffraction</i> ; November 8, 1993.
RRB	Kildemo, et al.; <i>Real Time Control of the Growth of Silicon Alloy Multilayers by Multiwavelength Ellipsometry</i> ; 1996.
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